PATENT PATENT

IN THE SPECIFICATION:

Please substitute the accompanying Substitute Specification for the original Specification. In accordance with 37 C.F.R. 1.125, the Substitute Specification has been submitted in clean form as a separate document and the specification paragraphs have been numbered as per 37 C.F.R. 1.52(b)(6). A marked-up version of the Substitute Specification follow the "Remarks" section of this amendment.

IN THE CLAIMS:

Please substitute the following clean amended claims 1-15, 18-38, 40-42, 44-46, 48-56, and 58-64, for the pending claims with the same number. A marked-up version of the amended claims follows the "Remarks" section of this amendment.

- 1. (Amended) A pattern forming method characterized by forming a mask having pattern-forming openings on a workpiece surface, and then supplying and solidifying a liquid pattern material in the pattern-forming openings of the mask.
- 2. (Amended) A pattern forming method comprising:
- a mask forming process for forming a mask having pattern-forming openings on a workpiece surface;
- a pattern material supplying process for supplying a liquid-pattern material to the pattern-forming openings while also drying the liquid-pattern material;
 - a process for removing the mask from the workpiece; and an annealing process for annealing dried solute of the liquid-pattern material.
- 3. (Amended) A pattern forming method comprising:
- a mask forming process for forming a mask having pattern-forming openings on a workpiece surface;
- a pattern material supplying process for supplying a liquid-pattern material to the pattern-forming openings;
 - a drying process for evaporating solvent in the liquid-pattern material;
 - a mask removal process for removing the mask from the workpiece; and an annealing process for annealing dried solute in the liquid-pattern material.
- 4. (Amended) A pattern forming method comprising:
- a mask forming process for forming a mask having pattern-forming openings on a workpiece surface;